

Towards 22% high-efficiency p-type PERC solar cells

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Passivated Emitter and Rear Cell (PERC)

The concept of advanced Si-based solar cells with a dielectric passivation layer at the rear of the cell is one of the most promising structures for changing the std. cell into a more-efficient PERC. The presence of a passivation layer at the rear of the cell permits low surface-recombination velocities, a steadier flow of electrons, and an improved performance. Consequently, excellent rear-surface passivation is one of the most important issues in improving the efficiency of PERC structures.

Loss analysis of PERCs

Saint-Cast et al. [1] conducted a loss analysis of PERCs and reported that

- more than half of the recombination events occur in the emitter and under the front contacts,
- second important loss channel is associated with passivation at the rear surface.

[1] P. Saint-Cast et al., Phys. Status Solidi A 214, 1600708 (2017).
 [2] A. Rohatgi et al., Proc. 17th EUPVSEC, 1307-1310 (2001).
 [3] B. Min et al., Energy Procedia 55, 115-120 (2014).

Ways towards 22% high-efficiency PERC

- Reducing recombination on the emitter and front metal grid by the implementation of a selective emitter (SE) structure [2, 3].
 - Selective emitter (SE) formation by wet chemical etch-back process
 - Rear surface passivation schemes
- Reducing recombination at rear structure
 - Local contact opening (LCO)
 - Rear surface passivation
 - Metallization material (Si-free Al paste, Al paste with Si)

SE PERC by etch-back

Selective emitter formation

Dipping time (s)	Final R_{sheet} (Ω/sq)
30	140

Dipping samples into etching solution

Legend: Al electrode, emitters, Al₂O₃, Ag electrode, SiNx, Si, Local back surface field

Effect of SE structure (Front)

SE with R_{sheet} for $n^{++}/n^+ = 60/125$ or $60/160$

With $V_{oc} = 665$ mV, $J_{sc} = 39.3$ mA/cm², FF = 80.4 %

Expected Eff > 21%

Efficiency improved!

[4] S. Joonwichien et al., IEEE J. Photovolt. 8, 703-709 (2018).

Effect of surface passiv. (Front)

A chemically grown SiO₂ layer by NAOS method

NAOS = Nitric acid oxidation of Si

	J_{sc}	V_{oc}	FF	Eff
Ref	38.4	651	79.6	19.9
With SiO ₂	38.5	656 (5 mV)	79.2	20.0

[5] S. Joonwichien et al., Sol. Energy Mater. Sol. Cells 186, 84-91 (2018).

Effect of LCO (Rear)

LCO shape	J_{sc}	V_{oc}	FF	Eff
Line	38.6	646	80.8	20.2
Dash	39.5	651	79.7	20.5

0.9 mA/cm² 5 mV

Dash-shaped LCO increases the passivation areas, thereby improved V_{oc} and J_{sc} .

Dot-shaped LCO for PERC can provide an additional 5 mV.

Effect of Si in Al paste (Rear)

All I-V improved Voids reduced 5 times (25% > 5%)

Al paste	J_{sc}	V_{oc}	FF	Eff
Si-free paste	37.8	635	78.7	18.9
Al paste + Si powder	38.3	645	81.1	20.1

0.5 mA/cm² 10 mV 2.4% 1.2%

Hypo-alloys Hyper-alloys

[6] S. Joonwichien et al., IEEE J. Photovolt. 8, 54-58 (2018).